

# **Nb/Cu coatings characterization in HiPIMS with biased substrate and application of a positive pulse**

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<sup>5</sup> CERN, EN/MME-MA

<sup>6</sup> CERN, EN/MME-MM

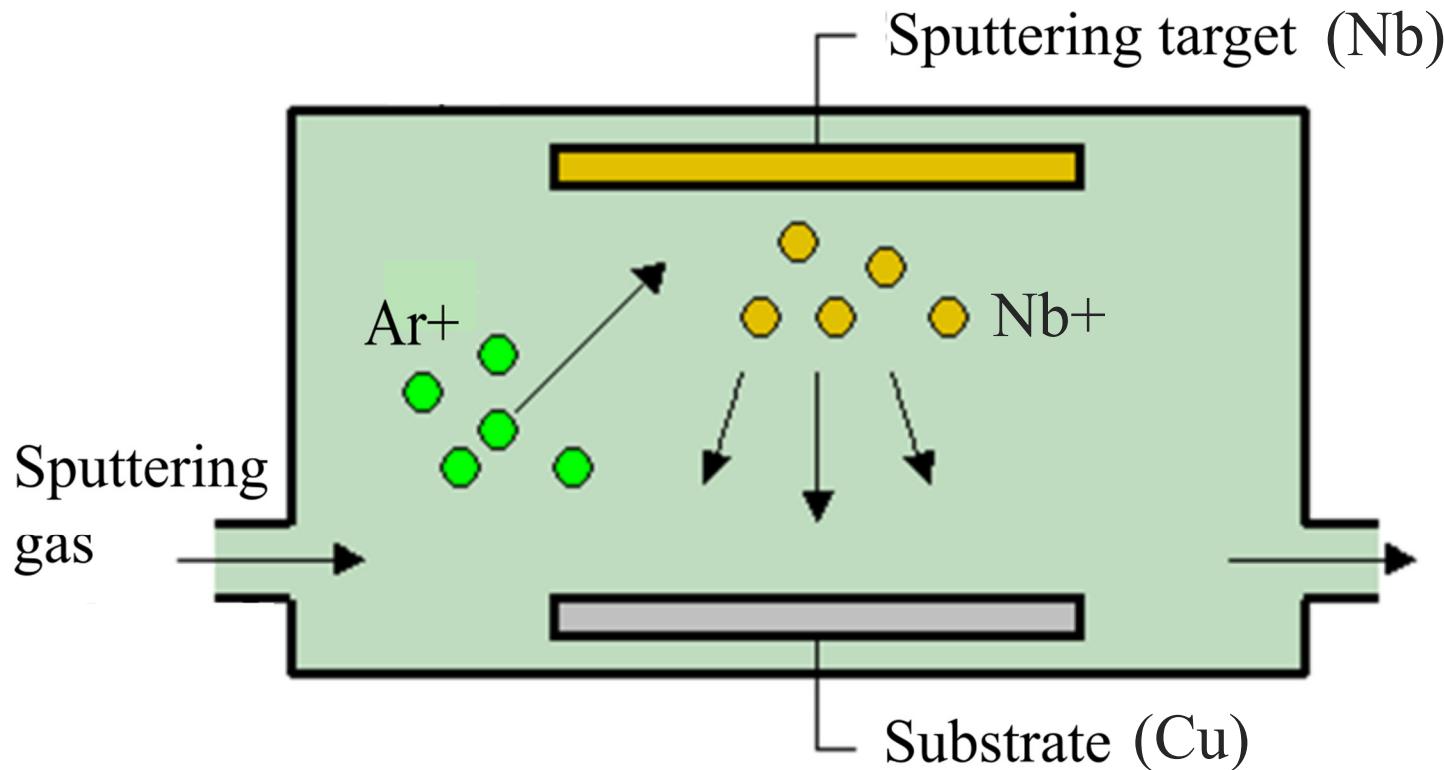
# Outline

- Why biased substrate & positive pulse?
- HiPIMS studies with positive pulse
  - Film morphology at grazing angles of incidence
  - Nb/Cu WOW crab cavity R&D
- HiPIMS studies with negatively biased substrate
  - Gas content with sync. biased substrate
  - Residual stress
- Conclusions

# Why biased substrate / positive pulse?

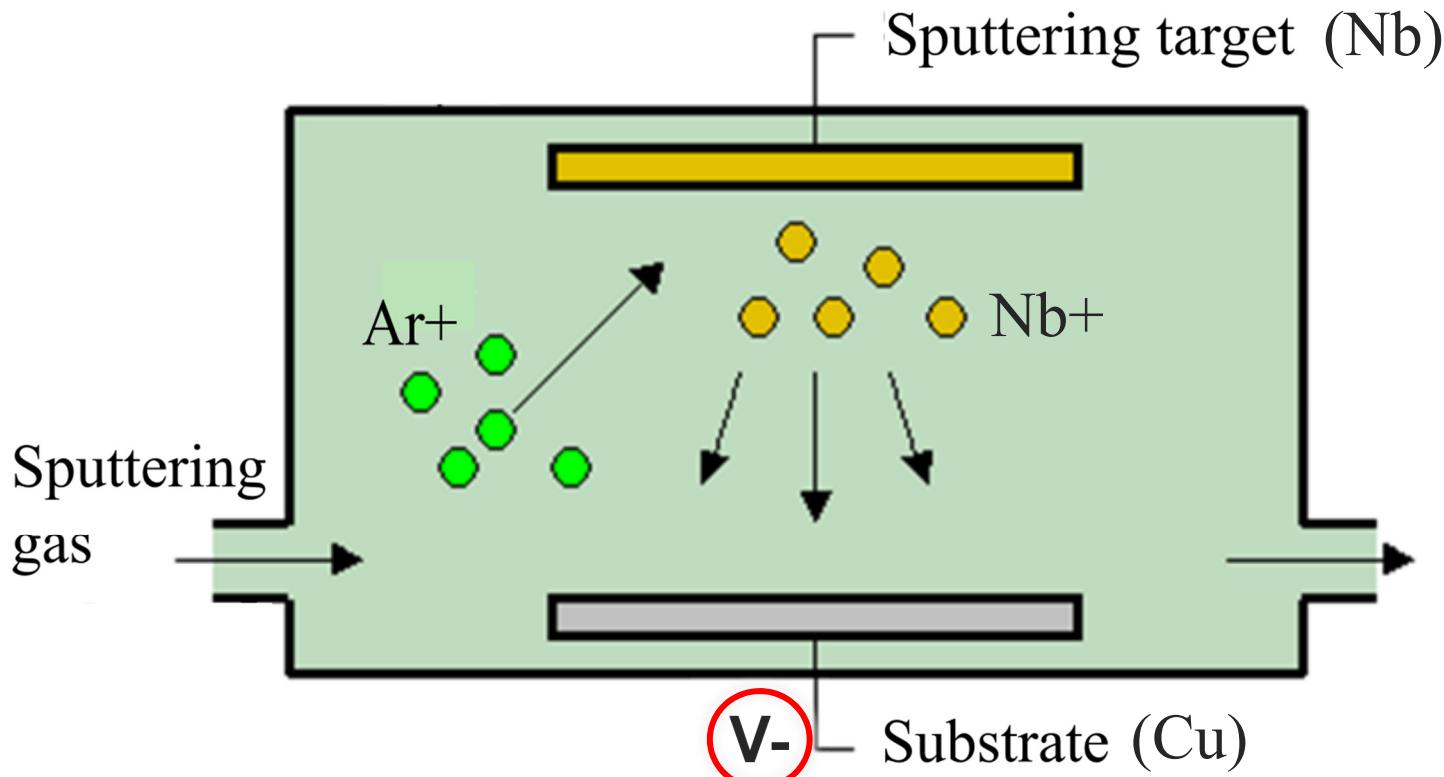
HiPIMS allows to get a higher fraction of metal ions wrt Direct Current Magnetron Sputtering.

How to accelerate the ions towards the substrate?



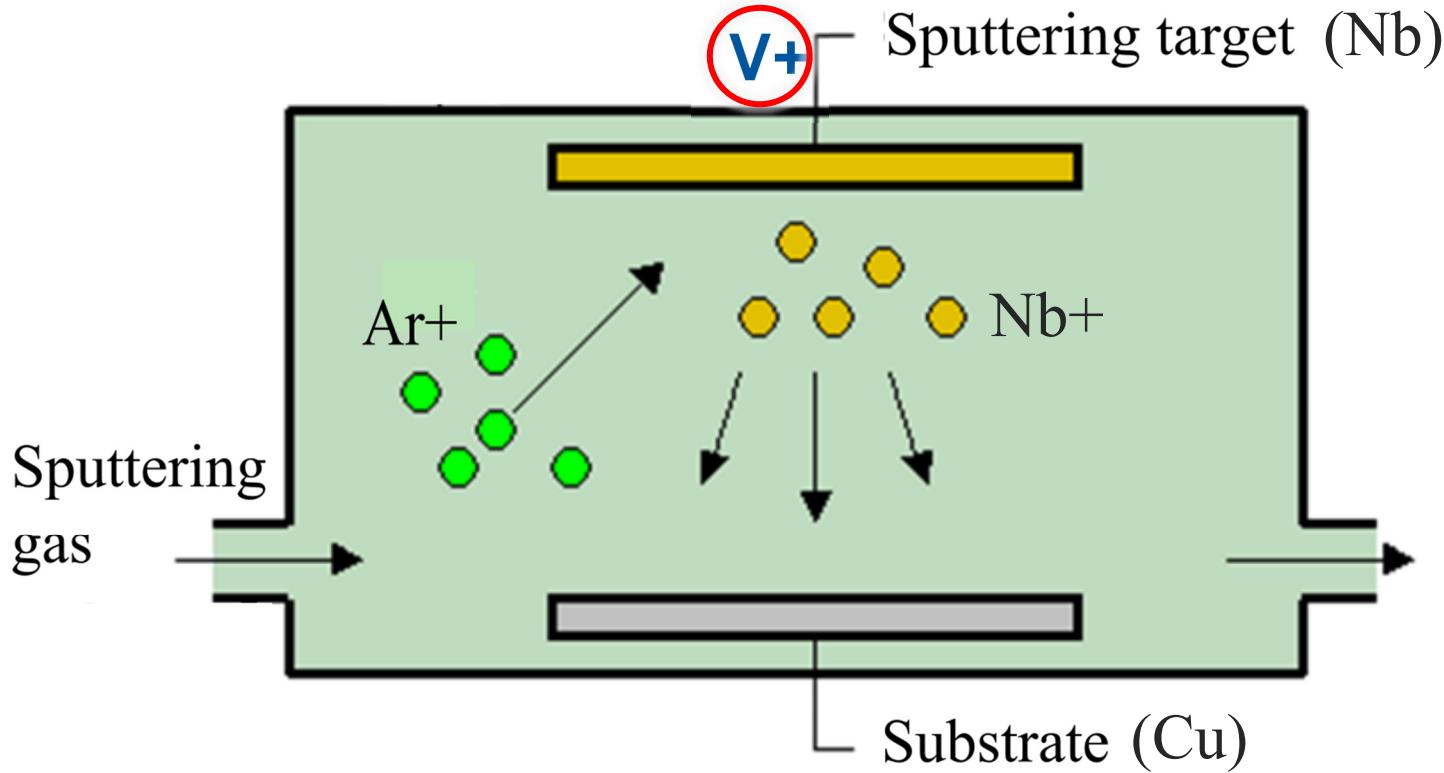
# Why biased substrate / positive pulse?

- By negatively biasing the substrate



# Why biased substrate / positive pulse?

- By negatively biasing the substrate
- By positive pulse (PP)

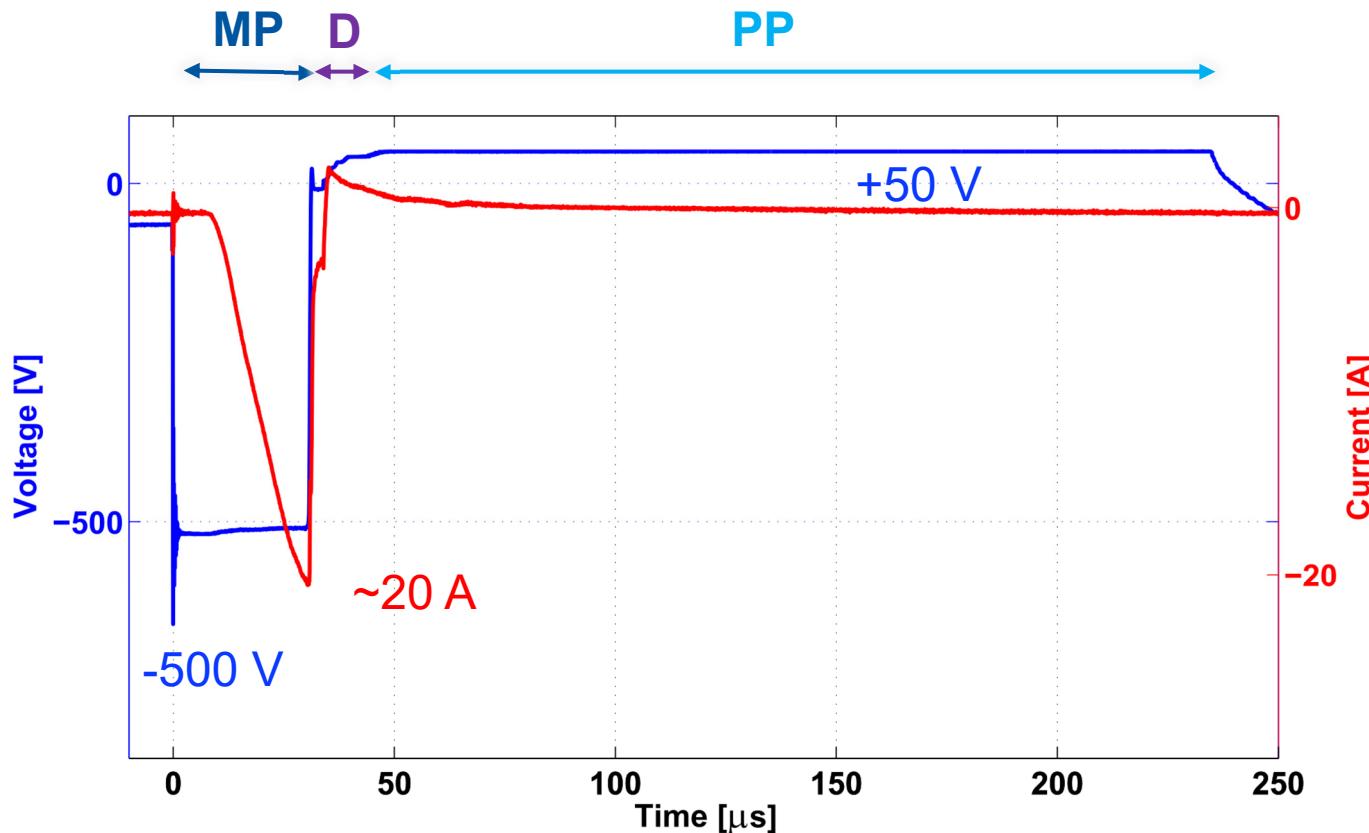


# HiPIMS configuration with PP

- Duty cycle : 1 kHz
- Main pulse (**MP**) : 30  $\mu$ s
- Delay (**D**) : 4  $\mu$ s
- Positive pulse (**PP**) : 200  $\mu$ s

PP advantages wrt biased substrate:

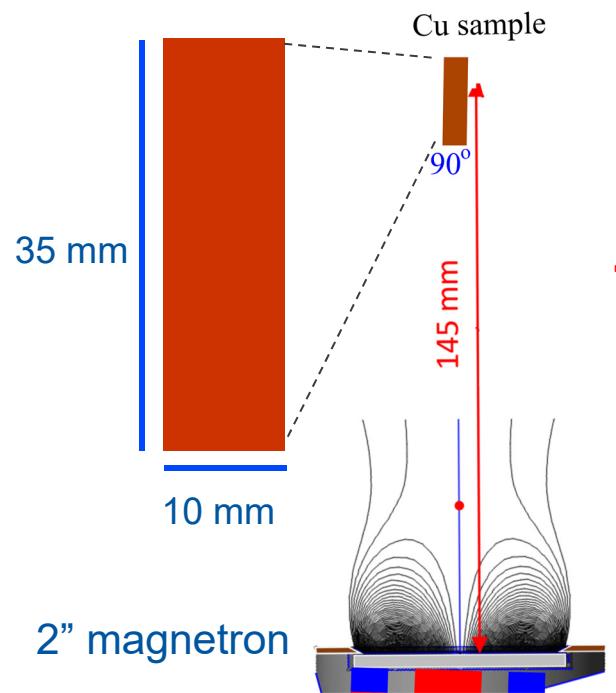
- Simplified magnetron design
- Grounded substrate



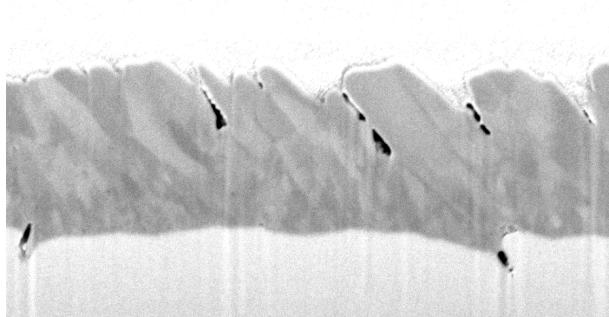
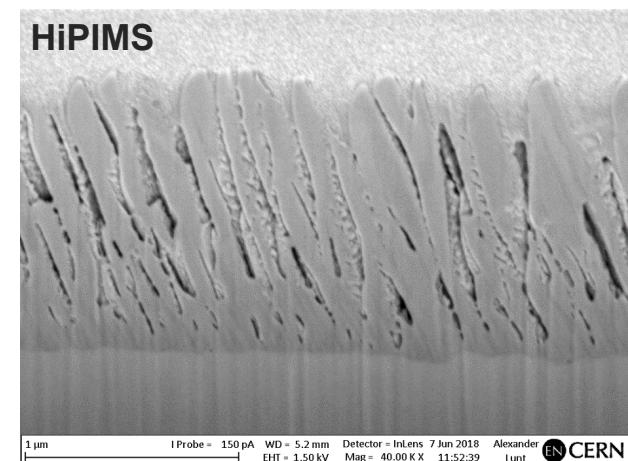
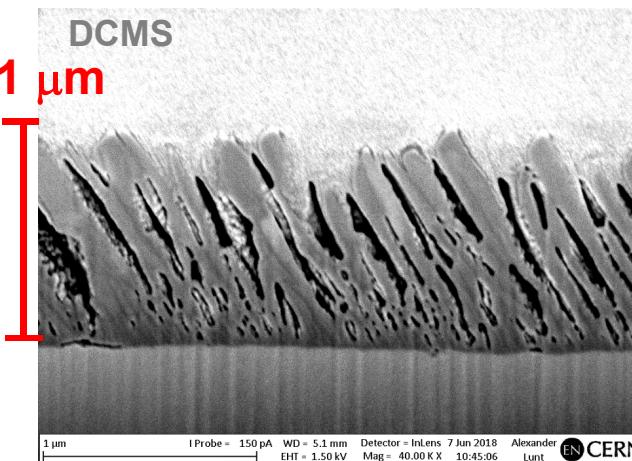
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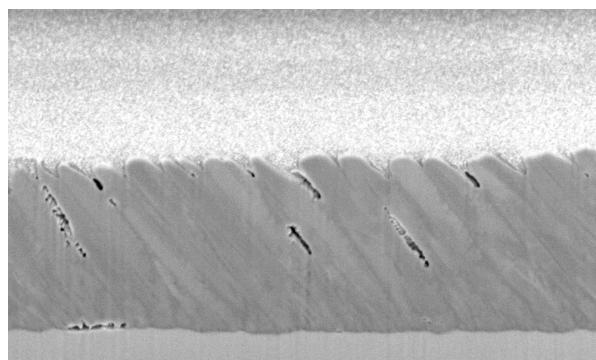
# FIB / Tc for samples at 90°



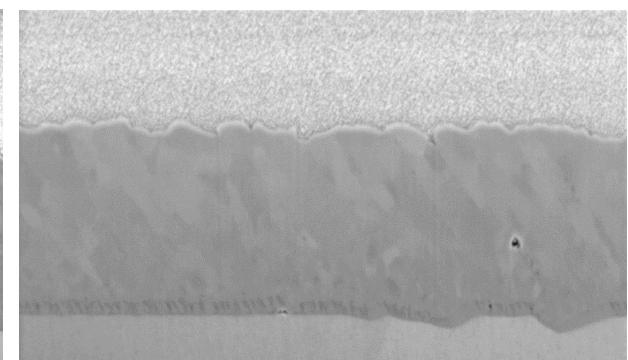
Ar pressure :  $8 \times 10^{-3}$  mbar



1 μm I Probe = 150 pA WD = 5.2 mm EHT = 1.50 kV Mag = 40.00 KX 15:50:30 Detector = InLens Alexander Lunt EN CERN



1 μm I Probe = 150 pA WD = 5.1 mm EHT = 1.50 kV Mag = 40.00 KX 16:03:57 Detector = InLens 25 Jun 2018 Alexander Lunt EN CERN



1 μm I Probe = 150 pA WD = 5.1 mm EHT = 1.50 kV Mag = 40.00 KX 14:23:53 Detector = InLens 25 Jun 2018 Alexander Lunt EN CERN

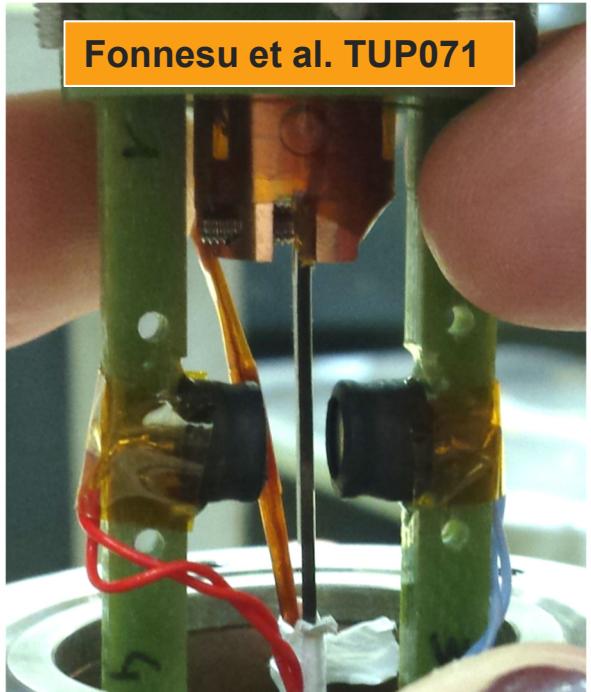
Films coated in HiPIMS + PP similar to HiPIMS + substrate bias!

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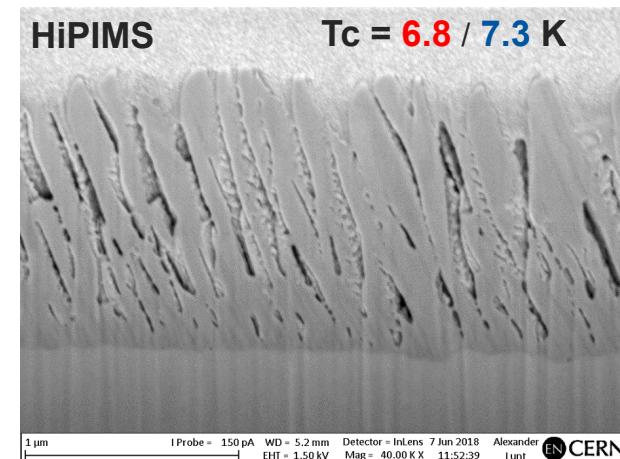
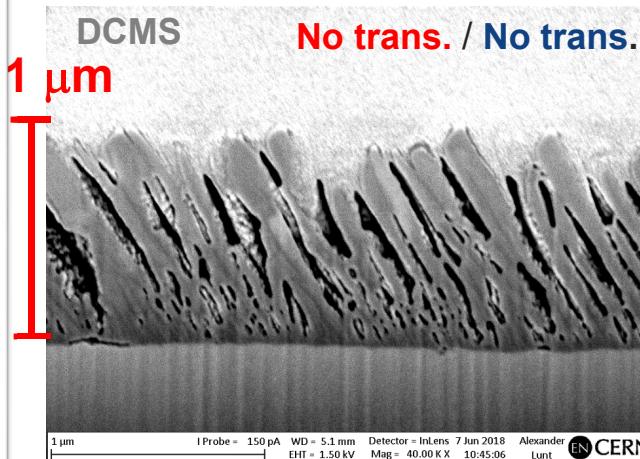


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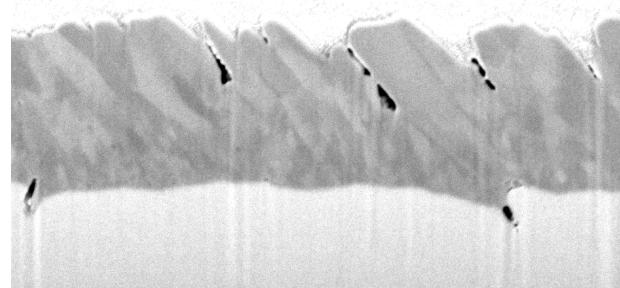
Fonnesu et al. TUP071



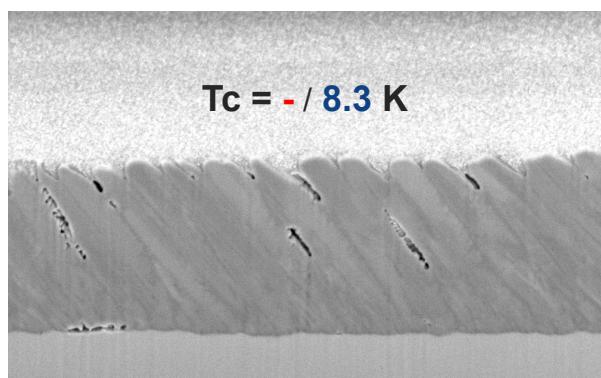
Ar pressure :  $8 \times 10^{-3}$  mbar



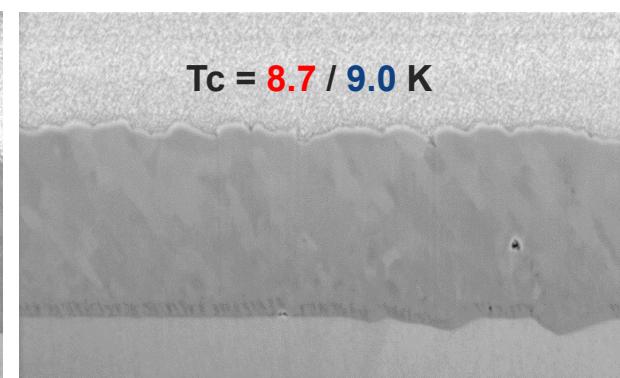
Tc = 8.6 / 8.9 K



HiPIMS, -50V substrate bias



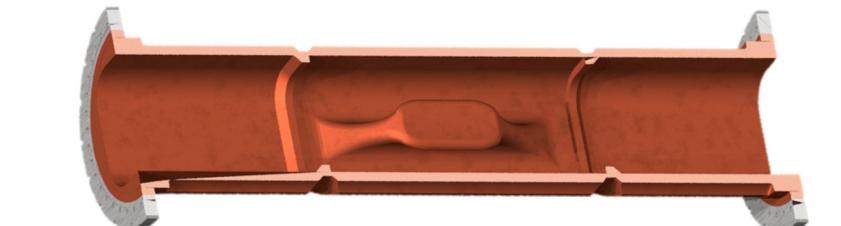
HiPIMS, +50V PP



HiPIMS, +100V PP

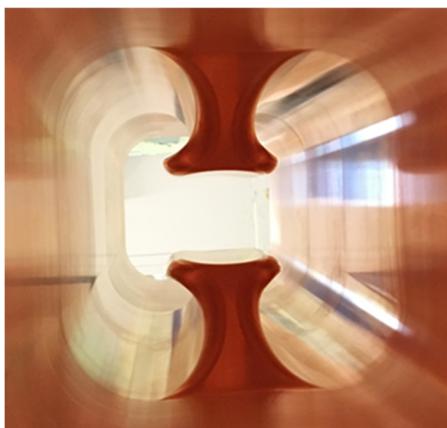
Films coated in HiPIMS + PP similar to HiPIMS + substrate bias!

# Nb/Cu Wide Open Waveguide crab cavity R&D



Front view

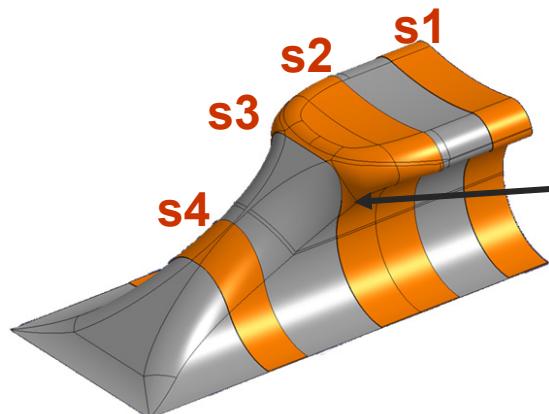
Detail of tapering



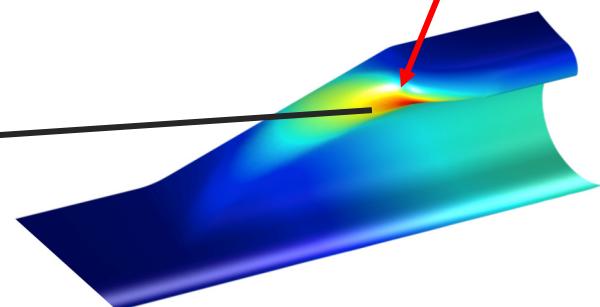
1.4m

Naïsson et al. MOP061

Mockup of 4 sections for coating R&D



Critical location of highest peak dissipated power

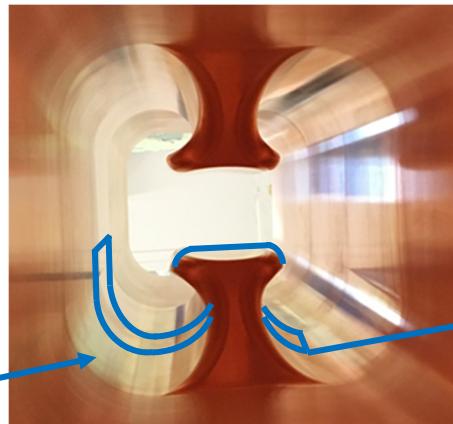
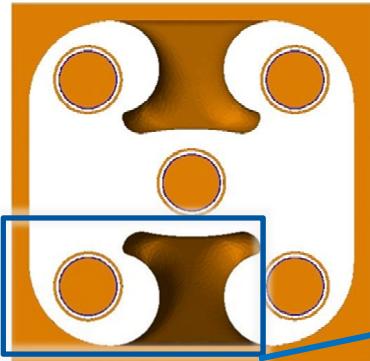


Total power loss  $\sim 60\text{W}$   
@  $Q_0 = 4 \times 10^8 / 3 \text{ MV deflection}$

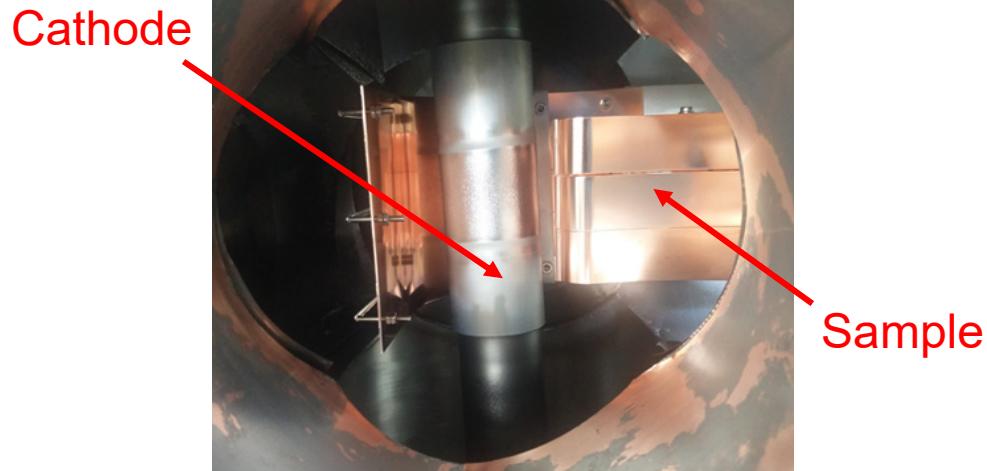
$\times 10^3$   
Dissipated  $P_{\text{surf}}$  [ $\text{W/m}^2$ ]

# First results on WOW crab cavity samples

Cathode positions  
under investigation



s1 sample: 1/4 of cavity

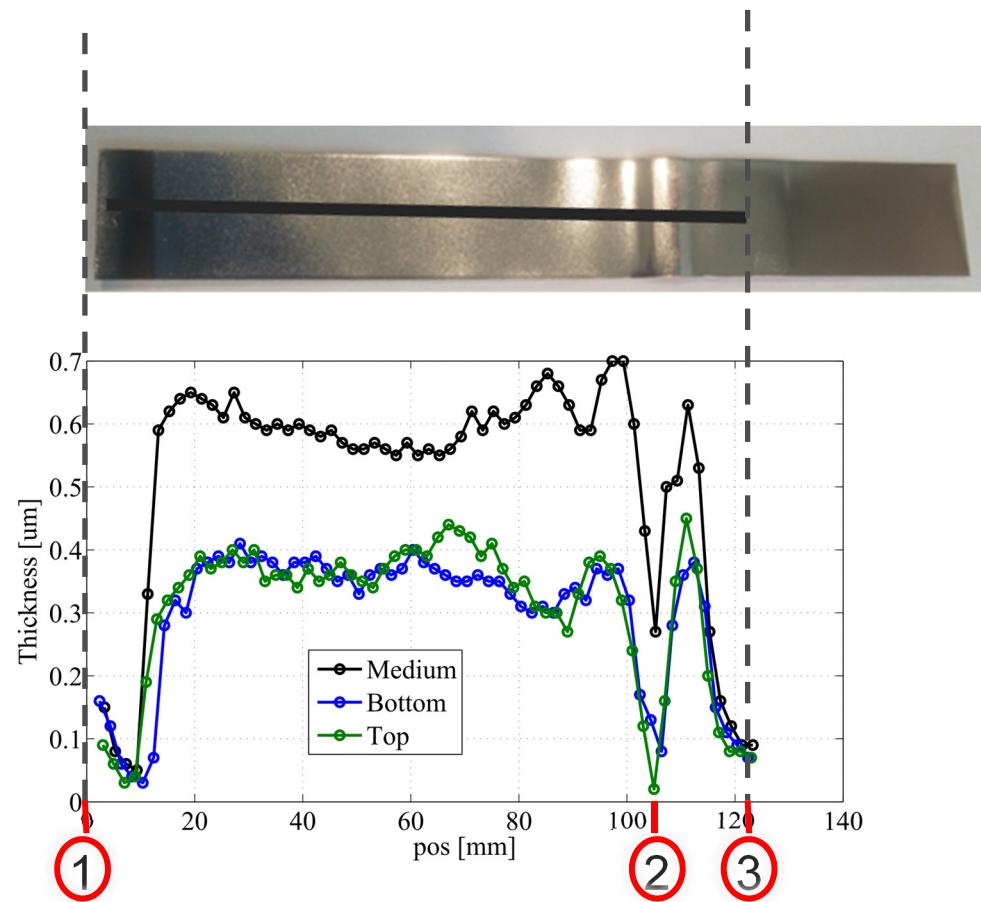
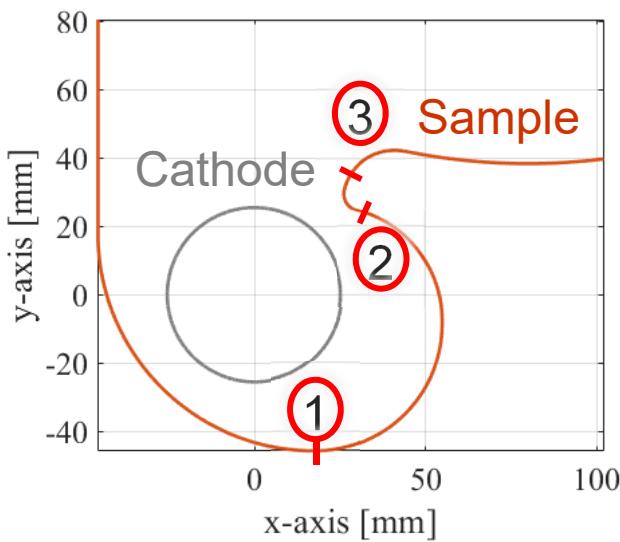
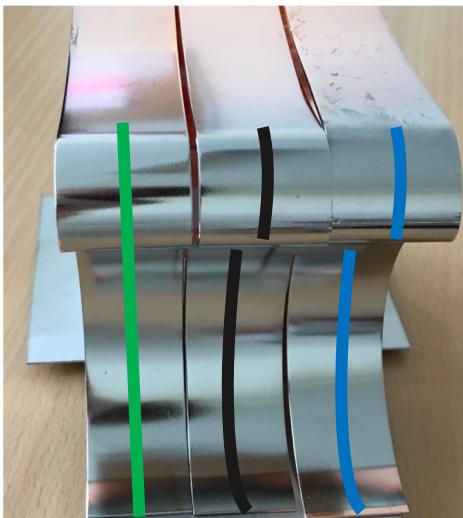


Assembly in coating chamber



Samples after coating  
HiPIMS+PP  
1kW, 6 minutes coating,

# XRF thickness profiles along sample length

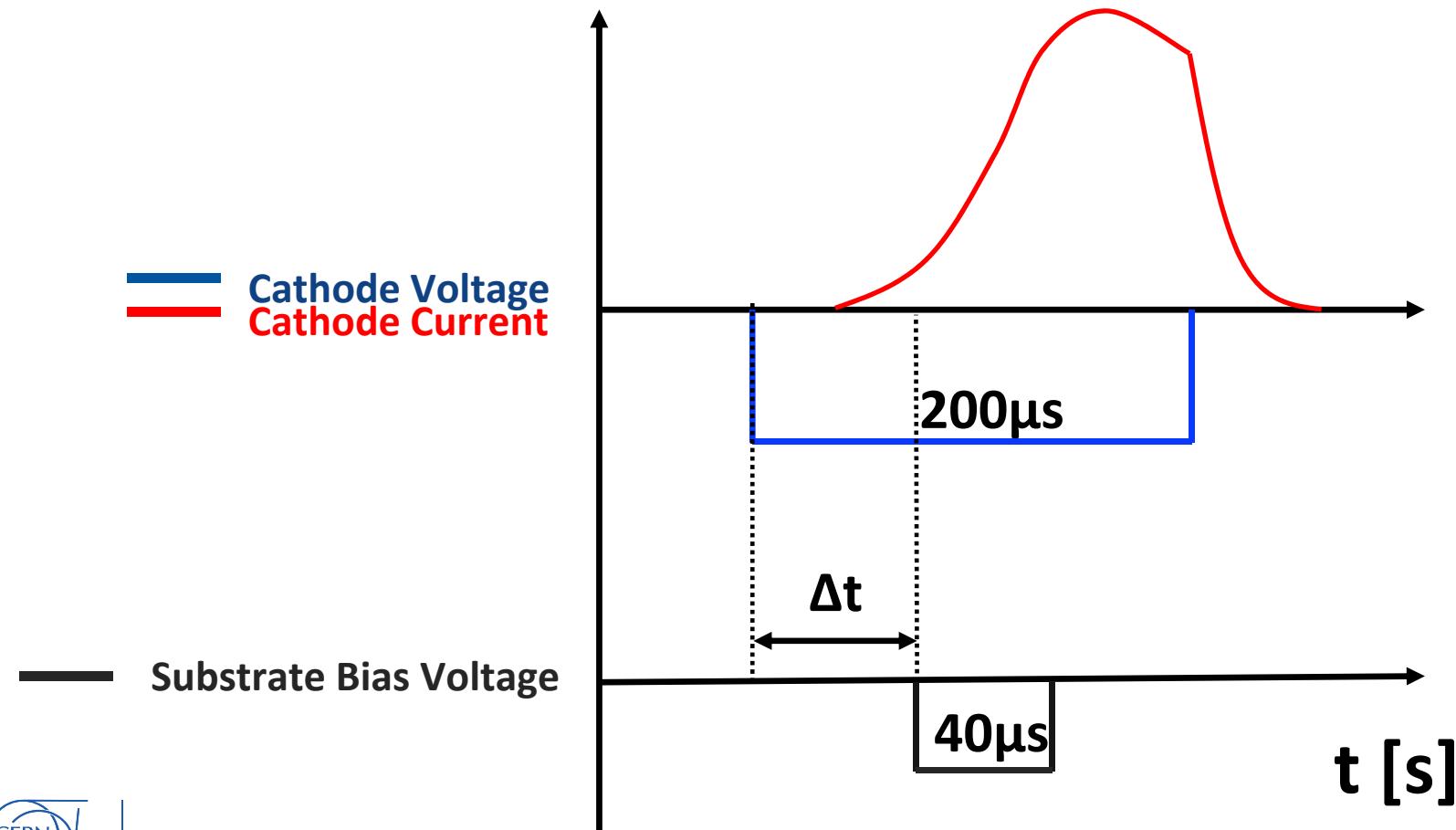


# Outline

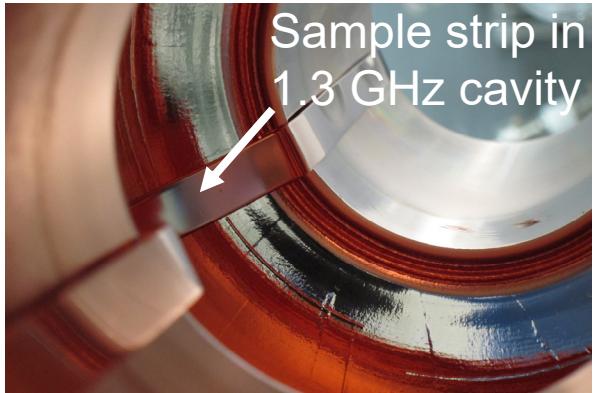
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# HiPIMS configuration with sync. biased substrate

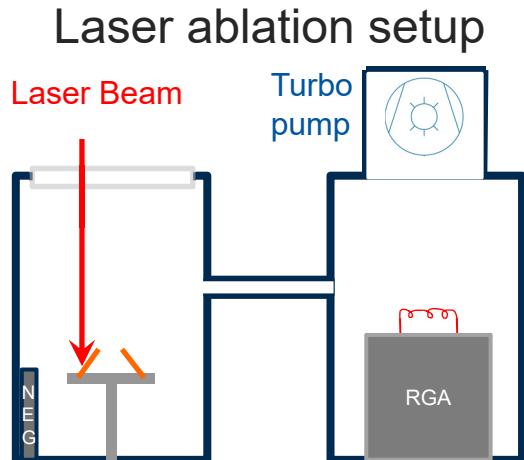
By accelerating metal ions, gas ions are accelerated too.  
How is the gas content varying by changing the triggering of the substrate bias?



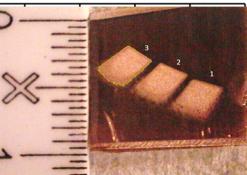
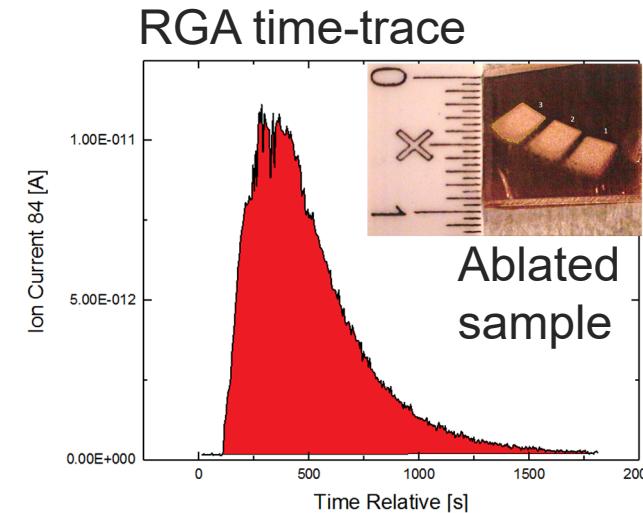
# Gas content with sync. biased



Sample strip in  
1.3 GHz cavity



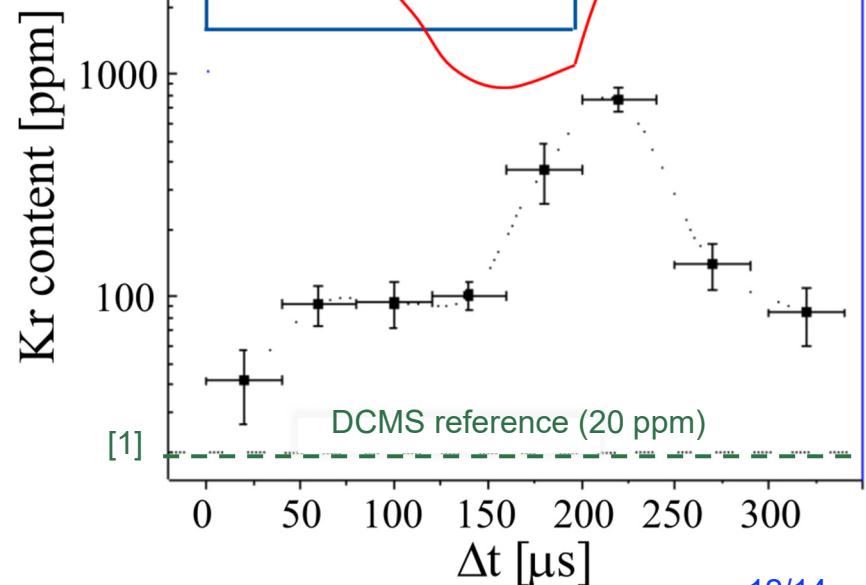
Laser ablation setup



Ablated  
sample

## Conclusions:

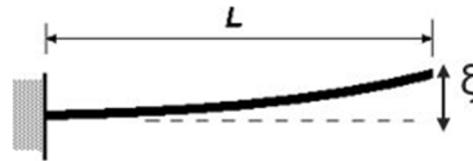
- Gas content can be « tuned » : variations within main pulse up to x22
- Impact on RF performances?



[1] AMOROSI, S., ANDERLE, Mariano, BENVENUTI, C., et al. Study of the discharge gas trapping during thin-film growth. *Vacuum*, 2001, vol. 60, no 1-2, p. 89-94.

# Residual stress analysis

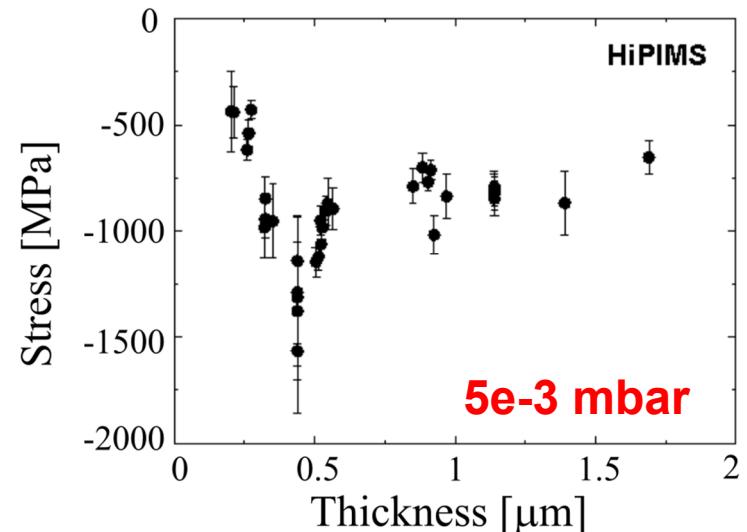
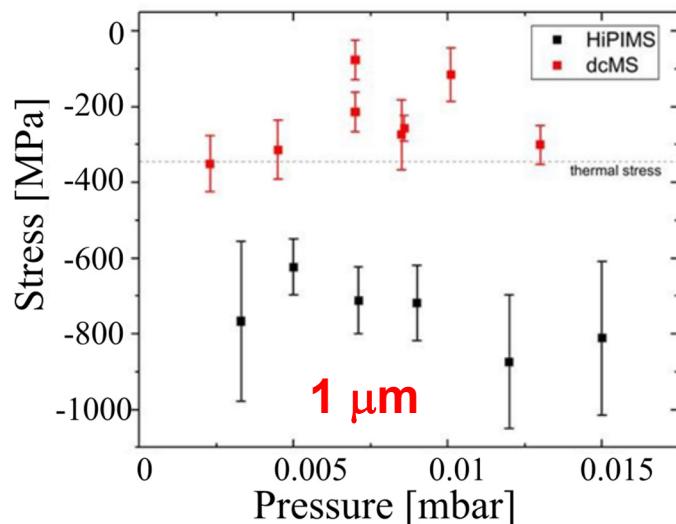
Is the stress responsible for the frequently observed peel-off in cavities?



Stoney's equation

$$\sigma = \frac{1}{6} \frac{E_s t_s^2}{(1 - \nu_s) R t_f} ; \quad R = \frac{L^2}{2\xi}$$

Young's modulus      Poisson's ratio



## Conclusions:

Significant higher level of stress (x2) in HiPIMS films for all coating pressures, but NO PEEL-OFF

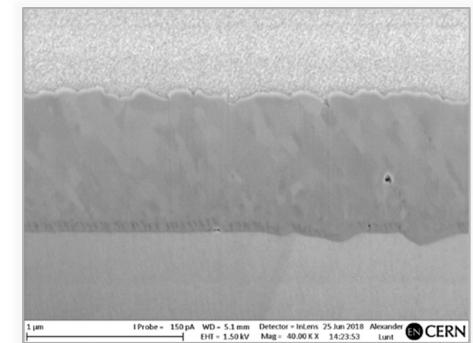
Beyond 500 nm residual stress saturates

Rosaz FRCAB2

# Conclusions

## HiPIMS + positive pulse (PP):

- Film densification for samples coated at grazing angles ( $90^\circ$ ) with PP, similarly to biased substrate.
- Preliminary results of films coated on samples with WOW crab cavity inner shape.



## HiPIMS + biased substrate:

- High Kr content in film with HiPIMS+biased substrate, but it can be tuned.
- Higher level of stress (up to x2) in HiPIMS films wrt DCMS for all coating pressures, but no peel-off.

